

AMENDMENTS TO THE ABSTRACT

Kindly replace the original abstract with the following substitute abstract.

~~The present invention relates to a~~ A substrate processing apparatus and a substrate processing method is provided for performing a chemical liquid process, a cleaning process, a drying process, or the like while rotating a substrate such as a semiconductor wafer or a liquid crystal substrate. ~~The present invention also relates to a~~ A substrate holding apparatus is provided for holding and rotating a substrate. The substrate processing apparatus ~~(1)~~ for processing a substrate ~~(W)~~ while supplying a fluid to the substrate ~~(W)~~ includes a substrate holder ~~(11)~~ for holding and rotating the substrate ~~(W)~~, and a holder suction unit ~~(24)~~ for sucking the fluid from the substrate holder ~~(11)~~. The substrate holding apparatus includes a plurality of rollers ~~(20)~~ which are brought into contact with an edge portion of a substrate ~~(W)~~ so as to hold and rotate the substrate ~~(W)~~, and at least one moving mechanism ~~(303a)~~ for moving the rollers ~~(20)~~.